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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Sheldon Aronowitz, Valeriy Sukharev,)
John Haywood, James P. Kimball,)
Helmut Puchner, Ravindra Manohar)
Kapre, and Nicholas Eib)
Filed: Herewith)
) Group Art Unit: Unknown
Serial Number: Unknown)
) Examiner: Unknown
Title: "Process for Etching a Controllable Thickness of Oxide)
on an Integrated Circuit Structure on a Semiconductor)
Substrate Using Nitrogen Plasma and an RF Bias)
Applied to the Substrate")

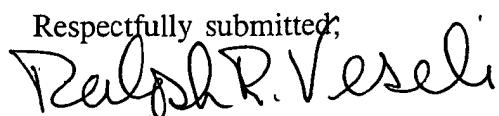
INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.56

Honorable Commissioner of Patents
and Trademarks
Washington, D.C. 20231

Date: 12/15/99

Sir:

Pursuant to 37 CFR 1.56, Applicants hereby submit the references listed on the attached form PTO-1449 (modified). Copies of each of the references are enclosed.

Respectfully submitted,

By: RALPH VESELI
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